What is claimed is

1. A cleaning liquid supplying system comprising:

a circulation line in which cleaning liquid flows, first end of the circulation line being connected to a supply port of a cleaning liquid supplying apparatus, second end of the circulation line being connected to a collection port of the cleaning liquid supplying apparatus;

a branch pipe branched from the circulation line and connected to a substrate cleaning unit;

a first valve provided on the branch pipe and configured to control supply of cleaning liquid from the circulation line to the substrate cleaning unit;

a nitrogen gas supplying source configured to supply nitrogen gas to the circulation line through a pipe;

a liquid supplying source configured to supply liquid that reacts with the cleaning liquid to the circulation line through the pipe:

a second valve provided on the pipe and configured to control supply of nitrogen gas from the nitrogen gas supplying source to the circulation line and supply of liquid from the liquid supplying source to the circulation line; and

a flow rate adjuster configured to adjust a flow rate of the cleaning liquid flowing in the circulation line.

2. The cleaning liquid supplying system according to claim 1, wherein the flow rate adjuster reduces the flow rate of the cleaning liquid flowing in the circulation line so as to suppress decrease of pressure in the circulation line even when

the valve is opened.

3. The cleaning liquid supplying system according to claim 1, further comprising a pressure gauge configured to measure pressure in the circulation line, wherein

the flow rate adjuster adjusts the flow rate of the cleaning liquid flowing in the circulation line based on the pressure in the circulation line.

4. The cleaning liquid supplying system according to claim 1, wherein the flow rate adjuster is an electric flow rate adjusting valve provided on the circulation line.